



Solutions for HIPIMS Processes

Gencoa Speedflo

Gencoa has developed sensor technology that enables the control of reactive HIPIMS processes for reproducible depositions and stable system performance. This is achieved through one of three methods: using a photomultiplier tube (PMT) with a electronic switch to detect the large light pulses; through inclusion of a CCD spectrometer; peak current sensor, a new type of non-optical sensor which detects the current peaks from the HIPIMS plasma.

- Control of HIPIMS processes
- Variable magnetic field properties
- Peak current control
- Optical emission for HIPIMS



Circular Vtech

Gencoa Vtech variable magnetrons are unique and powerful tools for advanced thin film development. The Vtech magnetrons allow the magnetic field strength and shape to be varied from outside the vacuum chamber before or during the process. This is a convenient method of changing the plasma properties and deliver optimum layer creation.

- Instant and simple adjustment
- Field strength and balance
- Dynamic adjustment during deposition process
- 2"-6" target diameter



3G Circular

Gencoa have developed a new third generation range of small circular magnetrons, all of which now include $\pm 45^\circ$ tilt adjustment, gas injection and a rear utility box for DC, DC-pulsed, RF and HIPIMS processes as standard.

- New HIPIMS-ready small circular
- Rear utility box as standard
- 2"-5" target diameter



Gencoa VTR

Gencoa VTR (VTEch by Rotation) is a new method for easy adjustment of the magnetic field from balanced to highly unbalanced. VTR offers benefits to hard, decorative or functional coatings, and is compatible with Gencoa's standard rectangular magnetrons, with no extra space requirements.

